L	Hits	Search Text	DB	Time stamp
Number	102005			
1	193095	(low adj k) sich sic sioc (silicon adj4 (dioxide carbon (carbon adj nitride)))	USPAT; US-PGPUB; EPO; JPO; DERWENT;	2004/11/02 09:00
2	1436474	semiconductor	IBM_TDB USPAT; US-PGPUB; EPO; JPO; DERWENT;	2004/11/02
3	6788	silicon with (diffused diffusion duffusing diffuse) with (metal cupper cu)	IBM_TDB USPAT; US-PGPUB; EPO; JPO; DERWENT;	2004/11/02 09:01
4	8283	(si silicon) with (diffused diffusion duffusing diffuse) with (metal cupper cu)	IBM_TDB USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2004/11/02 09:33
5	2356	((low adj k) sich sic sioc (silicon adj4 (dioxide carbon (carbon adj nitride)))) and semiconductor and ((si silicon) with (diffused diffusion duffusing diffuse) with (metal cupper cu))	USPAT; US-PGPUB; EPO; JPO; DERWENT;	2004/11/02 09:03
6	27783	diffusion with barrier	IBM_TDB USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2004/11/02 09:04
7	1241	<pre>(((low adj k) sicn sic sioc (silicon adj4 (dioxide carbon (carbon adj nitride)))) and semiconductor and ((si silicon) with (diffused diffusion duffusing diffuse) with (metal cupper cu))) and (diffusion with barrier)</pre>	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/11/02 09:04
8	37526	(etch etching etched) with (stop stopper stopped stopping)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2004/11/02 09:05
9	400	<pre>((((low adj k) sich sic sicc (silicon adj4 (dioxide carbon (carbon adj nitride)))) and semiconductor and ((si silicon) with (diffused diffusion duffusing diffuse) with (metal cupper cu))) and (diffusion with barrier)) and ((etch etching etched) with (stop stopper stopped stopping))</pre>	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/11/02
10	1094	(si silicon) with (diffused diffusion duffusing diffuse) with (cupper cu)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2004/11/02 10:10
11	156	<pre>((((((low adj k) sicn sic sioc (silicon adj4 (dioxide carbon (carbon adj nitride)))) and semiconductor and ((si silicon) with (diffused diffusion duffusing diffuse) with (metal cupper cu))) and (diffusion with barrier)) and ((etch etching etched) with (stop stopper stopped stopping))) and ((si silicon) with (diffused diffusion duffusing diffuse) with (cupper cu))</pre>	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/11/02 09:33
12	2685	(si silicon) with (diffused diffusion duffusing diffuse) with (copper cu)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/11/02 10:28

13	247	((si silicon) with (diffused diffusion	USPAT;	2004/11/02
		duffusing diffuse) with (copper cu)) and	US-PGPUB;	10:11
1		(((((low adj k) sich sic sioc (silicon	EPO; JPO;	
		adj4 (dioxide carbon (carbon adj	DERWENT;	
		nitride)))) and semiconductor and ((si	IBM TDB	ľ
		silicon) with (diffused diffusion	_	
		duffusing diffuse) with (metal cupper		
		cu))) and (diffusion with barrier)) and		
		((etch etching etched) with (stop stopper		
		stopped stopping)))		
14	91		USPAT;	2004/11/02
		duffusing diffuse) with (copper cu)) and	US-PGPUB;	10:12
		(((((low adj k) sich sic sioc (silicon	EPO; JPO;	
		adj4 (dioxide carbon (carbon adj	DERWENT;	
		nitride)))) and semiconductor and ((si	IBM TDB	
		silicon) with (diffused diffusion	1011_100	
		duffusing diffuse) with (metal cupper		
		cu))) and (diffusion with barrier)) and		
		((etch etching etched) with (stop stopper		
		stopped stopping)))) not (((((low adj k)		
		sich sic sioc (silicon adj4 (dioxide		
		carbon (carbon adj nitride)))) and		
,		semiconductor and ((si silicon) with		
		(diffused diffusion duffusing diffuse)		
		with (metal cupper cu))) and (diffusion		
1		with barrier)) and ((etch etching etched)		
[		<pre>with (stop stopper stopped stopping)))</pre>		j
j		and ((si silicon) with (diffused		ļ .
		diffusion duffusing diffuse) with (cupper		İ
		cu)))		
15	75	(,)- (	USPAT;	2004/11/02
		duffusing diffuse) adj2 (copper cu)	US-PGPUB;	10:29
			EPO; JPO;	
			DERWENT;	
			IBM TDB	
16	57	, , , ====:,) =	USPAT;	2004/11/02
,		duffusing diffuse) adj2 (copper cu)) and	US-PGPUB;	10:30
		((low adj k) sich sic sioc (silicon adj4	EPO; JPO;	
		(dioxide carbon (carbon adj nitride))))	DERWENT;	l l
		and semiconductor	IBM TDB	